

	Search Text
1	positive adj tone same (photoresist) same layer same (coat\$4 substrate)
2	positive adj tone same (photoresist) same layer same coat\$4 same substrate
3	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7)
4	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726"
5	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm)
6	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome
7	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block
8	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block\$4
9	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block\$4 and dry same etch\$5
10	(positive near5 tone) same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block\$4 and dry same etch\$5
11	(positive near5 tone) same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and attenuat\$5 same phase same shift\$5 and chrome and chrome near5 block\$4 and dry same etch\$5
12	(positive same tone same photoresist same (layer film coat\$4 substrate appl\$7)) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and attenuat\$5 same phase same shift\$5 and chrome and chrome near5 block\$4 and dry same etch\$5
13	"20040168147" and attenuat\$5
14	(positive same tone same photoresist same (layer film coat\$4 substrate appl\$7)) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm or alt adj (psm phase)) and attenuat\$5 same phase same shift\$5 and chrome and chrome near5 block\$4 and dry same etch\$5
15	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block\$4 and dry same etch\$5 and gate near3 (short\$6 shrink\$6 shrunk\$5 pull\$6)
16	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block\$4 and gate near3 (short\$6 shrink\$6 shrunk\$5 pull\$6)
17	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7) and @ad<"20020726" and ((alternat\$4 same phase same shift\$4 same mask) or apsm) and chrome and chrome near5 block\$4 and gate near3 (short\$6 shrink\$6 shrunk\$5 pull\$6)

	Search Text
18	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7 film)
19	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7 film) and (alternat\$4 same phase same shift\$5)
20	positive adj tone same (photoresist) same (layer coat\$4 substrate appl\$7 film) and (alternat\$4 same phase same shift\$5) and attenuat\$4 same phase same shift\$5
21	(positive near3 tone) same (photoresist photo adj resist) same (layer coat\$4 substrate appl\$7 film) and (alternat\$4 same phase same shift\$5) and (attenuat\$4 same phase same shift\$5 same gate same (pull\$4 short\$8 shrink\$5 shrunk\$4))
22	"20040168147" and positive adj tone
23	(positive adj tone) with (photoresist photo adj resist) near4 (layer coat\$4 substrate appl\$7 film)
24	(positive near3 tone) same (photoresist photo adj resist) same (layer coat\$4 substrate appl\$7 film) and (alternat\$4 same phase same shift\$5) and (attenuat\$4 same phase same shift\$5) and gate near2 (pull\$4 short\$8 shrink\$5 shrunk\$4)
25	(positive near3 tone) same (photoresist photo adj resist) same (layer coat\$4 substrate appl\$7 film) and (alternat\$4 same phase same shift\$5) and (attenuat\$4 same phase same shift\$5) and gate near2 (pull\$4 short\$8 shrink\$5 shrunk\$4) and dry\$4 same etch\$4
26	width and (scattering adj bar assist\$4 adj feature)
27	width and (scattering adj bar assist\$4 adj feature) and alternat\$4 same phase same shift\$4
28	width and (scattering adj bar assist\$4 adj feature) and alternat\$4 same phase same shift\$4 and attenuat\$4 same phase same shift\$4
29	width and (scattering adj bar assist\$4 adj feature) and alternat\$4 same phase same shift\$4 and attenuat\$4 same phase same shift\$4 and gate with (pull\$5 short\$6 shrunk\$6 shrink\$5)
30	width and (scattering adj bar assist\$4 adj feature) and alternat\$4 same phase same shift\$4 and attenuat\$4 same phase same shift\$4 and gate with (pull\$5 short\$6 shrunk\$6 shrink\$5) and @ad<"20020726"
31	alternat\$4 same phase same shift\$4 and attenuat\$4 same phase same shift\$4 and gate with (pull\$5 short\$6 shrunk\$6 shrink\$5) and @ad<"20020726"
32	alternat\$4 same phase same shift\$4 and attenuat\$4 same phase same shift\$4 and gate with (pull\$5 short\$6 shrunk\$6 shrink\$5) and @ad<"20020726" and (dry with etch\$4 or positive adj tone)
33	(alternat\$4 same phase same shift\$4 and attenuat\$4 same phase same shift\$4 and gate with (pull\$5 short\$6 shrunk\$6 shrink\$5) and (drysame etch\$4) and (positive same tone)).clm.